

EUROPEAN PATENT OFFICE
U.S. PATENT AND TRADEMARK OFFICE

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

The following classification changes will be effected by this Notice of Changes:

<u>Action</u>	<u>Subclass</u>	<u>Group(s)</u>
SCHEME:		
Symbols Deleted:	G03F	2007/2067
Symbols New:	G03F	7/70504, 7/70605, 7/70653, 7/70655, 7/70681, 7/706831, 7/706833, 7/706835, 7/706837, 7/706839, 7/706841, 7/706843, 7/706845, 7/706847, 7/706849, 7/706851
Titles Changed:	G03F	7/70, 7/70016, 7/70025, 7/70033, 7/70041, 7/7005, 7/70066, 7/70075, 7/70091, 7/70108, 7/70116, 7/70141, 7/70166, 7/70175, 7/70183, 7/70191, 7/702, 7/70208, 7/70216, 7/70225, 7/70233, 7/70241, 7/7025, 7/70258, 7/70266, 7/70275, 7/70283, 7/70291, 7/703, 7/70308, 7/70316, 7/70325, 7/70333, 7/70341, 7/7035, 7/70375, 7/70383, 7/70391, 7/70408, 7/70416, 7/70425, 7/70433, 7/70441, 7/7045, 7/70458, 7/70466, 7/70483, 7/70491, 7/705, 7/70508, 7/70516, 7/70525, 7/70533, 7/70541, 7/7055, 7/70558, 7/70575, 7/70583, 7/70591, 7/706, 7/70608, 7/70616, 7/70625, 7/70633, 7/70641, 7/7065, 7/70658, 7/70666, 7/70675, 7/70683, 7/70691, 7/707, 7/70708, 7/70716, 7/70758, 7/70775, 7/70783, 7/70791, 7/708, 7/70808, 7/70816, 7/70825, 7/70833, 7/70841, 7/70875, 7/709, 7/70908, 7/70925, 7/70933, 7/70958, 7/70975, 7/70991
Indents Changed:	G03F	7/70383, 7/70391, 7/704, 7/70408, 7/70416, 7/70608, 7/70616, 7/70625, 7/70633, 7/70641, 7/7065, 7/70658, 7/70666, 7/70675, 7/70683
Warnings New:	B29C	64/00
	G03F	7/70, 7/70375, 7/70416, 7/70483, 7/70491, 7/705, 7/70504, 7/70508, 7/70516, 7/70525, 7/70533, 7/70605, 7/70608, 7/70616, 7/70625, 7/70633, 7/70641, 7/7065, 7/70653, 7/70655, 7/70658, 7/70666, 7/70675, 7/70681, 7/70683, 7/706831, 7/706833, 7/706835, 7/706839, 7/706843, 7/706845, 7/706847, 7/706849, 7/706851
Notes Modified:	G03F	7/70416

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Action</u>	<u>Subclass</u>	<u>Group(s)</u>
DEFINITIONS:		
Definitions Deleted: (no frozen (F) symbol definitions should be deleted)	G03F	2007/2067

The following subclasses/groups are also impacted by this Notice of Changes (indicate subclasses/groups outside of the project scope, such as those listed in the CRL): B81C, F16C, G03F, H01J

This Notice of Changes includes the following [Check the ones included]:

1. CLASSIFICATION SCHEME CHANGES

- A. New, Modified or Deleted Group(s)
- B. New, Modified or Deleted Warning(s)
- C. New, Modified or Deleted Note(s)
- D. New, Modified or Deleted Guidance Heading(s)

2. DEFINITIONS

- A. New or Modified Definitions (Full definition template)
- B. Modified or Deleted Definitions (Definitions Quick Fix)

3. REVISION CONCORDANCE LIST (RCL)

4. CHANGES TO THE CPC-TO-IPC CONCORDANCE LIST (CICL)

5. CHANGES TO THE CROSS-REFERENCE LIST (CRL)

DATE: MAY 1, 2023

PROJECT RP10475

1. CLASSIFICATION SCHEME CHANGES

A. New, Modified or Deleted Group(s)**SUBCLASS G03F - PHOTOMECHANICAL PRODUCTION OF TEXTURED OR PATTERNED SURFACES, e.g. FOR PRINTING, FOR PROCESSING OF SEMICONDUCTOR DEVICES; MATERIALS THEREFOR; ORIGINALS THEREFOR; APPARATUS SPECIALLY ADAPTED THEREFOR**

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to[#]</u>
D	G03F 2007/2067	2	{Apparatus for microlithography}	<administrative transfer to G03F7/70>
T	G03F 7/70	1	{Microphotolithographic exposure; Apparatus therefor (photo-masks G03F 1/00)}	
M	G03F 7/70016	3	{by discharge lamps}	
M	G03F 7/70025	3	{by lasers}	
M	G03F 7/70033	3	{by plasma extreme ultraviolet [EUV] sources}	
M	G03F 7/70041	3	{by pulsed sources, e.g. multiplexing, pulse duration, interval control or intensity control}	
M	G03F 7/7005	3	{by multiple sources, e.g. light-emitting diodes [LED] or light source arrays (addressable array sources specially adapted to produce patterns without a mask G03F 7/70391)}	
U	G03F 7/70058	2	{Mask illumination systems}	
M	G03F 7/70066	3	{Size and form of the illuminated area in the mask plane, e.g. reticle masking blades or blinds}	
M	G03F 7/70075	3	{Homogenization of illumination intensity in the mask plane by using an integrator, e.g. fly’s eye lens, facet mirror or glass rod, by using a diffusing optical element or by beam deflection}	
M	G03F 7/70091	3	{Illumination settings, i.e. intensity distribution in the pupil plane or angular distribution in the field plane; On-axis or off-axis settings, e.g. annular, dipole or quadrupole settings; Partial coherence control, i.e. sigma or numerical aperture [NA]}	
M	G03F 7/70108	4	{Off-axis setting using a light-guiding element, e.g. diffractive optical elements [DOEs] or light guides}	

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

Type*	Symbol	Indent Level Number of dots (e.g. 0, 1, 2)	Title <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	Transferred to#
M	G03F 7/70116	4	{Off-axis setting using a programmable means, e.g. liquid crystal display [LCD], digital micromirror device [DMD] or pupil facets}	
M	G03F 7/70141	3	{Illumination system adjustment, e.g. adjustments during exposure or alignment during assembly of illumination system}	
U	G03F 7/7015	3	{Details of optical elements}	
M	G03F 7/70166	4	{Capillary or channel elements, e.g. nested extreme ultraviolet [EUV] mirrors or shells, optical fibers or light guides}	
M	G03F 7/70175	4	{Lamphouse reflector arrangements or collector mirrors, i.e. collecting light from solid angle upstream of the light source}	
M	G03F 7/70183	4	{Zoom systems for adjusting beam diameter}	
M	G03F 7/70191	3	{Optical correction elements, filters or phase plates for controlling intensity, wavelength, polarisation, phase or the like}	
M	G03F 7/702	3	{Reflective illumination, i.e. reflective optical elements other than folding mirrors, e.g. extreme ultraviolet [EUV] illumination systems}	
M	G03F 7/70208	3	{Multiple illumination paths, e.g. radiation distribution devices, microlens illumination systems, multiplexers or demultiplexers for single or multiple projection systems}	
M	G03F 7/70216	2	{Mask projection systems}	
M	G03F 7/70225	3	{Optical aspects of catadioptric systems, i.e. comprising reflective and refractive elements}	
M	G03F 7/70233	3	{Optical aspects of catoptric systems, i.e. comprising only reflective elements, e.g. extreme ultraviolet [EUV] projection systems}	
M	G03F 7/70241	3	{Optical aspects of refractive lens systems, i.e. comprising only refractive elements}	
M	G03F 7/7025	3	{Size or form of projection system aperture, e.g. aperture stops, diaphragms or pupil obscuration; Control thereof}	

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
M	G03F 7/70258	3	{Projection system adjustments, e.g. adjustments during exposure or alignment during assembly of projection system}	
M	G03F 7/70266	4	{Adaptive optics, e.g. deformable optical elements for wavefront control, e.g. for aberration adjustment or correction}	
M	G03F 7/70275	3	{Multiple projection paths, e.g. array of projection systems, microlens projection systems or tandem projection systems}	
M	G03F 7/70283	3	{Mask effects on the imaging process}	
M	G03F 7/70291	4	{Addressable masks, e.g. spatial light modulators [SLMs], digital micro-mirror devices [DMDs] or liquid crystal display [LCD] patterning devices}	
M	G03F 7/703	3	{Non-planar pattern areas or non-planar masks, e.g. curved masks or substrates}	
M	G03F 7/70308	3	{Optical correction elements, filters or phase plates for manipulating imaging light, e.g. intensity, wavelength, polarisation, phase or image shift}	
M	G03F 7/70316	3	{Details of optical elements, e.g. of Bragg reflectors, extreme ultraviolet [EUV] multilayer or bilayer mirrors or diffractive optical elements}	
M	G03F 7/70325	3	{Resolution enhancement techniques not otherwise provided for, e.g. darkfield imaging, interfering beams, spatial frequency multiplication, nearfield lenses or solid immersion lenses}	
M	G03F 7/70333	4	{Focus drilling, i.e. increase in depth of focus for exposure by modulating focus during exposure [FLEX]}	
M	G03F 7/70341	3	{Details of immersion lithography aspects, e.g. exposure media or control of immersion liquid supply (chemical composition of immersion liquids G03F 7/2041)}	
M	G03F 7/7035	3	{Proximity or contact printers}	
U	G03F 7/70358	3	{Scanning exposure, i.e. relative movement of patterned beam and workpiece during imaging}	
C	G03F 7/70375	2	{Multiphoton lithography or multiphoton photopolymerization; Imaging systems comprising means for converting one	G03F7/70375, G03F7/70

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
			type of radiation into another type of radiation}	
M	G03F 7/70383	2	{Direct write, i.e. pattern is written directly without the use of a mask by one or multiple beams (maskless lithography using a programmable mask G03F 7/70291)}	
M	G03F 7/70391	3	{Addressable array sources specially adapted to produce patterns, e.g. addressable LED arrays}	
M	G03F 7/704	3	{Scanned exposure beam, e.g. raster-, rotary- and vector scanning (mask projection exposure involving relative movement of patterned beam and workpiece during imaging G03F 7/70358)}	
M	G03F 7/70408	2	{Interferometric lithography; Holographic lithography; Self-imaging lithography, e.g. utilizing the Talbot effect}	
C	G03F 7/70416	2	{2.5D lithography}	G03F7/70416, B29C64/00, B29C64/10, B29C64/106, B29C64/112, B29C64/118, B29C64/124, B29C64/129, B29C64/135, B29C64/141, B29C64/147, B29C64/153, B29C64/159, B29C64/165, B29C64/171, B29C64/176, B29C64/182, B29C64/188, B29C64/194, B29C64/20, B29C64/205, B29C64/209, B29C64/214, B29C64/218, B29C64/223, B29C64/227,

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
				B29C64/232, B29C64/236, B29C64/241, B29C64/245, B29C64/25, B29C64/255, B29C64/259, B29C64/264, B29C64/268, B29C64/273, B29C64/277, B29C64/282, B29C64/286, B29C64/291, B29C64/295, B29C64/30, B29C64/307, B29C64/314, B29C64/321, B29C64/329, B29C64/336, B29C64/343, B29C64/35, B29C64/357, B29C64/364, B29C64/371, B29C64/379, B29C64/386, B29C64/393, B29C64/40
M	G03F 7/70425	2	{Imaging strategies, e.g. for increasing throughput or resolution, printing product fields larger than the image field or compensating lithography- or non-lithography errors, e.g. proximity correction, mix-and-match, stitching or double patterning}	
M	G03F 7/70433	3	{Layout for increasing efficiency or for compensating imaging errors, e.g. layout of exposure fields for reducing focus errors; Use of mask features for increasing efficiency or for compensating imaging errors}	
M	G03F 7/70441	4	{Optical proximity correction [OPC]}	
M	G03F 7/7045	3	{Hybrid exposures, i.e. multiple exposures of the same area using	

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
			different types of exposure apparatus, e.g. combining projection, proximity, direct write, interferometric, UV, x-ray or particle beam}	
M	G03F 7/70458	3	{Mix-and-match, i.e. multiple exposures of the same area using a similar type of exposure apparatus, e.g. multiple exposures using a UV apparatus}	
M	G03F 7/70466	3	{Multiple exposures, e.g. combination of fine and coarse exposures, double patterning or multiple exposures for printing a single feature (stitching G03F 7/70475)}	
C	G03F 7/70483	2	{Information management; Active and passive control; Testing; Wafer monitoring, e.g. pattern monitoring}	G03F7/70483, G03F7/70605, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F 7/70491	3	{Information management, e.g. software; Active and passive control, e.g. details of controlling exposure processes or exposure tool monitoring processes}	G03F7/70491, G03F7/70605, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706845
C	G03F 7/705	4	{Modelling or simulating from physical phenomena up to complete wafer processes or whole workflow in wafer productions}	G03F 7/705, G03F 7/70504, G03F7/70605, G03F7/70653, G03F7/70681, G03F7/70683, G03F7/706831,

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
				G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845
N	G03F 7/70504	5	{Optical system modelling, e.g. lens heating models}	
C	G03F 7/70508	4	{Data handling in all parts of the microlithographic apparatus, e.g. handling pattern data for addressable masks or data transfer to or from different components within the exposure apparatus}	G03F7/70508, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706845
C	G03F 7/70516	4	{Calibration of components of the microlithographic apparatus, e.g. light sources, addressable masks or detectors}	G03F7/70516, G03F7/70653, G03F7/70655, G03F7/706845
C	G03F 7/70525	4	{Controlling normal operating mode, e.g. matching different apparatus, remote control or prediction of failure}	G03F7/70525, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841
C	G03F 7/70533	4	{Controlling abnormal operating mode, e.g. taking account of waiting time, decision to rework or rework flow}	G03F7/70533, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841
M	G03F 7/70541	4	{Tagging, i.e. hardware or software tagging of features or components, e.g. using tagging scripts or tagging identifier codes for identification of chips, shots or wafers}	
M	G03F 7/7055	3	{Exposure light control in all parts of the microlithographic apparatus, e.g. pulse length control or light interruption}	
M	G03F 7/70558	4	{Dose control, i.e. achievement of a desired dose}	
M	G03F 7/70575	4	{Wavelength control, e.g. control of bandwidth, multiple wavelength, selection of wavelength or matching of optical components to wavelength}	
M	G03F 7/70583	4	{Speckle reduction, e.g. coherence control or amplitude/wavefront splitting}	

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
M	G03F 7/70591	3	{Testing optical components}	
M	G03F 7/706	4	{Aberration measurement}	
N	G03F 7/70605	3	{Workpiece metrology}	
C	G03F 7/70608	4	{Monitoring the unpatterned workpiece, e.g. measuring thickness, reflectivity or effects of immersion liquid on resist}	G03F7/70608, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F 7/70616	4	{Monitoring the printed patterns}	G03F7/70616, G03F7/70653, G03F7/70655, G03F7/70666, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F 7/70625	5	{Dimensions, e.g. line width, critical dimension [CD], profile, sidewall angle or edge roughness}	G03F7/70625, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845,

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
				G03F7/706847, G03F7/706849, G03F7/706851
C	G03F 7/70633	5	{Overlay, i.e. relative alignment between patterns printed by separate exposures in different layers, or in the same layer in multiple exposures or stitching}	G03F7/70633, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F 7/70641	5	{Focus}	G03F7/70641, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F 7/7065	5	{Defects, e.g. optical inspection of patterned layer for defects}	G03F7/7065, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847,

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
				G03F7/706849, G03F7/706851
N	G03F 7/70653	4	{Metrology techniques}	
N	G03F 7/70655	5	{Non-optical, e.g. atomic force microscope [AFM] or critical dimension scanning electron microscope [CD-SEM]}	
C	G03F 7/70658	5	{Electrical testing}	G03F7/70658, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845
C	G03F 7/70666	5	{Aerial image, i.e. measuring the image of the patterned exposure light at the image plane of the projection system}	G03F7/70666, G03F7/70681, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841
C	G03F 7/70675	5	{Latent image, i.e. measuring the image of the exposed resist prior to development}	G03F7/70675, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
N	G03F 7/70681	4	{Metrology strategies}	
C	G03F 7/70683	5	{Mark designs}	G03F7/70683, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845
N	G03F 7/706831	5	{Recipe selection or optimisation, e.g. select or optimise recipe parameters such	

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
			as wavelength, polarisation or illumination modes}	
N	G03F 7/706833	5	{Sampling plan selection or optimisation, e.g. select or optimise the number, order or locations of measurements taken per die, workpiece, lot or batch}	
N	G03F 7/706835	4	{Metrology information management or control}	
N	G03F 7/706837	5	{Data analysis, e.g. filtering, weighting, flyer removal, fingerprints or root cause analysis}	
N	G03F 7/706839	5	{Modelling, e.g. modelling scattering or solving inverse problems}	
N	G03F 7/706841	6	{Machine learning}	
N	G03F 7/706843	4	{Metrology apparatus}	
N	G03F 7/706845	5	{Calibration, e.g. tool-to-tool calibration, beam alignment, spot position or focus}	
N	G03F 7/706847	5	{Production of measurement radiation, e.g. synchrotron, free-electron laser, plasma source or higher harmonic generation [HHG]}	
N	G03F 7/706849	5	{Irradiation branch, e.g. optical system details, illumination mode or polarisation control}	
N	G03F 7/706851	5	{Detection branch, e.g. detector arrangements, polarisation control, wavelength control or dark/bright field detection}	
M	G03F 7/70691	2	{Handling of masks or workpieces}	
M	G03F 7/707	3	{Chucks, e.g. chucking or un-chucking operations or structural details}	
M	G03F 7/70708	4	{being electrostatic; Electrostatically deformable vacuum chucks}	
M	G03F 7/70716	3	{Stages}	
M	G03F 7/70758	3	{Drive means, e.g. actuators, motors for long- or short-stroke modules or fine or coarse driving}	
M	G03F 7/70775	3	{Position control, e.g. interferometers or encoders for determining the stage position}	
M	G03F 7/70783	3	{Handling stress or warp of chucks, masks or workpieces, e.g. to compensate for imaging errors or considerations related to warpage of masks or workpieces due to their own weight}	

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

Type*	Symbol	Indent Level Number of dots (e.g. 0, 1, 2)	Title “CPC only” text should normally be enclosed in {curly brackets}**	Transferred to#
M	G03F 7/70791	3	{Large workpieces, e.g. glass substrates for flat panel displays or solar panels}	
M	G03F 7/708	2	{Construction of apparatus, e.g. environment aspects, hygiene aspects or materials}	
M	G03F 7/70808	3	{Construction details, e.g. housing, load-lock, seals or windows for passing light in or out of apparatus}	
M	G03F 7/70816	4	{Bearings}	
M	G03F 7/70825	4	{Mounting of individual elements, e.g. mounts, holders or supports (workpiece or mask holders G03F 7/707)}	
M	G03F 7/70833	4	{Mounting of optical systems, e.g. mounting of illumination system, projection system or stage systems on base-plate or ground}	
M	G03F 7/70841	4	{Constructional issues related to vacuum environment, e.g. load-lock chamber}	
M	G03F 7/70875	5	{Temperature, e.g. temperature control of masks or workpieces via control of stage temperature}	
M	G03F 7/709	4	{Vibration, e.g. vibration detection, compensation, suppression or isolation}	
M	G03F 7/70908	3	{Hygiene, e.g. preventing apparatus pollution, mitigating effect of pollution or removing pollutants from apparatus}	
M	G03F 7/70925	4	{Cleaning, i.e. actively freeing apparatus from pollutants, e.g. using plasma cleaning}	
M	G03F 7/70933	4	{Purge, e.g. exchanging fluid or gas to remove pollutants}	
M	G03F 7/70958	4	{Optical materials or coatings, e.g. with particular transmittance, reflectance or anti-reflection properties}	
M	G03F 7/70975	3	{Assembly, maintenance, transport or storage of apparatus}	
M	G03F 7/70991	3	{Connection with other apparatus, e.g. multiple exposure stations, particular arrangement of exposure apparatus and pre-exposure and/or post-exposure apparatus; Shared apparatus, e.g. having shared radiation source, shared mask or workpiece stage, shared base-plate; Utilities, e.g. cable, pipe or wireless	

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Symbol</u>	<u>Indent Level Number of dots (e.g. 0, 1, 2)</u>	<u>Title</u> <u>“CPC only” text should normally be enclosed in {curly brackets}**</u>	<u>Transferred to#</u>
			arrangements for data, power, fluids or vacuum}	

*N = new entries where reclassification into entries is involved; C = entries with modified file scope where reclassification of documents from the entries is involved; Q = new entries which are firstly populated with documents via administrative transfers from deleted (D) entries. Afterwards, the transferred documents into the Q entry will either stay or be moved to more appropriate entries, as determined by intellectual reclassification; T= existing entries with enlarged file scope, which receive documents from C or D entries, e.g. when a limiting reference is removed from the entry title; M = entries with no change to the file scope (no reclassification); D = deleted entries; F = frozen entries will be deleted once reclassification of documents from the entries is completed; U = entries that are unchanged.

NOTES:

- **No {curly brackets} are used for titles in CPC only subclasses, e.g. C12Y, A23Y; 2000 series symbol titles of groups found at the end of schemes (orthogonal codes); or the Y section titles. The {curly brackets} are used for 2000 series symbol titles found interspersed throughout the main trunk schemes (breakdown codes).
- U groups: it is obligatory to display the required “anchor” symbol (U group), i.e. the entry immediately preceding a new group or an array of new groups to be created (in case new groups are not clearly subgroups of C-type groups). Always include the symbol, indent level and title of the U group in the table above.
- All entry types should be included in the scheme changes table above for better understanding of the overall scheme change picture. Symbol, indent level, and title are required for all types.
- “Transferred to” column must be completed for all C, D, F, and Q type entries. F groups will be deleted once reclassification is completed.
- When multiple symbols are included in the “Transferred to” column, avoid using ranges of symbols in order to be as precise as possible.
- For administrative transfer of documents, the following text should be used: “< administrative transfer to XX>”, “<administrative transfer to XX and YY simultaneously>”, or “<administrative transfer to XX, YY, ...and ZZ simultaneously>” when administrative transfer of the same documents is to more than one place.
- Administrative transfer to main trunk groups is assumed to be the source allocation type, unless otherwise indicated.
- Administrative transfer to 2000/Y series groups is assumed to be “additional information”.
- If needed, instructions for allocation type should be indicated within the angle brackets using the abbreviations “ADD” or “INV”: <administrative transfer to XX ADD>, <administrative transfer to XX INV>, or < administrative transfer to XX ADD, YY INV, ... and ZZ ADD simultaneously>.
- In certain situations, the “D” entries of 2000-series or Y-series groups may not require a destination (“Transferred to”) symbol, however it is required to specify “<no transfer>” in the “Transferred to” column for such cases.
- For finalisation projects, the deleted “F” symbols should have <no transfer> in the “Transferred to” column.
- For more details about the types of scheme change, see CPC Guide.

DATE: MAY 1, 2023

PROJECT RP10475

B. New, Modified or Deleted Warning(s)

SUBCLASS B29C - SHAPING OR JOINING OF PLASTICS; SHAPING OF MATERIAL IN A PLASTIC STATE, NOT OTHERWISE PROVIDED FOR; AFTER-TREATMENT OF THE SHAPED PRODUCTS, e.g. REPAIRING

<u>Type*</u>	<u>Location</u>	<u>Old Warning</u>	<u>New/Modified Warning</u>
N	B29C 64/00		Groups B29C 64/00 - B29C 64/40 are incomplete pending reclassification of documents from group G03F 7/70416. All groups listed in this Warning should be considered in order to perform a complete search.

SUBCLASS G03F - PHOTOMECHANICAL PRODUCTION OF TEXTURED OR PATTERNED SURFACES, e.g. FOR PRINTING, FOR PROCESSING OF SEMICONDUCTOR DEVICES; MATERIALS THEREFOR; ORIGINALS THEREFOR; APPARATUS SPECIALLY ADAPTED THEREFOR

<u>Type*</u>	<u>Location</u>	<u>Old Warning</u>	<u>New/Modified Warning</u>
N	G03F 7/70		Group G03F 7/70 is incomplete pending reclassification of documents from group G03F 7/70375. Groups G03F 7/70375 and G03F 7/70 should be considered in order to perform a complete search.
N	G03F 7/70375		Group G03F 7/70375 is impacted by reclassification into group G03F 7/70. Groups G03F 7/70375 and G03F 7/70 should be considered in order to perform a complete search.
N	G03F 7/70416		Group G03F 7/70416 is impacted by reclassification into groups B29C 64/00 - B29C 64/40. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70483		Group G03F 7/70483 is impacted by reclassification into groups G03F 7/70605, G03F 7/70653, G03F 7/70655, G03F 7/70681, G03F 7/706831, G03F 7/706833, G03F 7/706835 - G03F 7/706841 and G03F 7/706843 - G03F 7/706851. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70491		Group G03F 7/70491 is impacted by reclassification into groups G03F 7/70605, G03F 7/70681, G03F 7/706831, G03F 7/706833,

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Location</u>	<u>Old Warning</u>	<u>New/Modified Warning</u>
			G03F 7/706835 - G03F 7/706841 and G03F 7/706845. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/705		Group G03F 7/705 is impacted by reclassification into groups G03F 7/70504, G03F 7/70605, G03F 7/70653, G03F 7/70681- G03F 7/706833, G03F 7/706835 - G03F 7/706841, G03F 7/706843 and G03F 7/706845. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70504		Group G03F 7/70504 is incomplete pending reclassification of documents from group G03F 7/705. Groups G03F 7/705 and G03F 7/70504 should be considered in order to perform a complete search.
N	G03F 7/70508		Group G03F 7/70508 is impacted by reclassification into groups G03F 7/70681, G03F 7/706831, G03F 7/706833, G03F 7/706835, G03F 7/706837 and G03F 7/706845. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70516		Group G03F 7/70516 is impacted by reclassification into groups G03F 7/70653, G03F 7/70655 and G03F 7/706845. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70525		Group G03F 7/70525 is impacted by reclassification into groups G03F 7/706835 - G03F 7/706841. Groups G03F 7/70525 and G03F 7/706835 - G03F 7/706841 should be considered in order to perform a complete search.
N	G03F 7/70533		Group G03F 7/70533 is impacted by reclassification into groups G03F 7/706835 - G03F 7/706841. Groups G03F 7/70533 and G03F 7/706835 - G03F 7/706841 should be considered in order to perform a complete search.

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Location</u>	<u>Old Warning</u>	<u>New/Modified Warning</u>
N	G03F 7/70605		Group G03F 7/70605 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70491 and G03F 7/705. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70608		Group G03F 7/70608 is impacted by reclassification into groups G03F 7/70653, G03F 7/70655, G03F 7/70681, G03F 7/706831, G03F 7/706833, G03F 7/706835 - G03F 7/706841 and G03F 7/706843 - G03F 7/706851. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70616		Group G03F 7/70616 is impacted by reclassification into groups G03F 7/70653, G03F 7/70655, G03F 7/70666, G03F 7/70681, G03F 7/706831, G03F 7/706833, G03F 7/706835 - G03F 7/706841 and G03F 7/706843 - G03F 7/706851. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70625		Group G03F 7/70625 is impacted by reclassification into groups G03F 7/70653, G03F 7/70655, G03F 7/70681, G03F 7/706831, G03F 7/706833, G03F 7/706835 - G03F 7/706841 and G03F 7/706843 - G03F 7/706851. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70633		Group G03F 7/70633 is impacted by reclassification into groups G03F 7/70653, G03F 7/70655, G03F 7/70681, G03F 7/706831, G03F 7/706833, G03F 7/706835 - G03F 7/706841 and G03F 7/706843 - G03F 7/706851. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70641		Group G03F 7/70641 is impacted by reclassification into groups G03F 7/70653, G03F 7/70655, G03F 7/70681, G03F 7/706831, G03F 7/706833, G03F 7/706835 -

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Location</u>	<u>Old Warning</u>	<u>New/Modified Warning</u>
			G03F 7/706841 and G03F 7/706843 - G03F 7/706851. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/7065		Group G03F 7/7065 is impacted by reclassification into groups G03F 7/70653, G03F 7/70655, G03F 7/70681, G03F 7/706831, G03F 7/706833, G03F 7/706835 - G03F 7/706841 and G03F 7/706843 - G03F 7/706851. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70653		Group G03F 7/70653 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/705, G03F 7/70516, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641 and G03F 7/7065. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70655		Group G03F 7/70655 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70516, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641 and G03F 7/7065. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70658		Group G03F 7/70658 is impacted by reclassification into groups G03F 7/706833, G03F 7/706835 - G03F 7/706841, G03F 7/706843 and G03F 7/706845. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70666		Group G03F 7/70666 is incomplete pending reclassification of documents from group G03F 7/70616. Group G03F 7/70666 is also impacted by reclassification into groups G03F 7/70681 and G03F 7/706835-G03F 7/706841.

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Location</u>	<u>Old Warning</u>	<u>New/Modified Warning</u>
			All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70675		Group G03F 7/70675 is impacted by reclassification into groups G03F 7/706831, G03F 7/706833, G03F 7/706835 - G03F 7/706841 and G03F 7/706843 - G03F 7/706851. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70681		Group G03F 7/70681 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70491, G03F 7/705, G03F 7/70508, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065 and G03F 7/70666. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/70683		Group G03F 7/70683 is incomplete pending reclassification of documents from group G03F 7/705. Group G03F 7/70683 is also impacted by reclassification into groups G03F 7/706831, G03F 7/706833, G03F 7/706835 - G03F 7/706841, G03F 7/706843 and G03F 7/706845. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706831		Group G03F 7/706831 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70491, G03F 7/705, G03F 7/70508, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065, G03F 7/70675 and G03F 7/70683. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706833		Group G03F 7/706833 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70491, G03F 7/705, G03F 7/70508, G03F 7/70608, G03F 7/70616, G03F 7/70625,

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Location</u>	<u>Old Warning</u>	<u>New/Modified Warning</u>
			G03F 7/70633, G03F 7/70641, G03F 7/7065, G03F 7/70658, G03F 7/70675 and G03F 7/70683. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706835		Groups G03F 7/706835 and G03F 7/706837 are incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70491, G03F 7/705, G03F 7/70508, G03F 7/70525, G03F 7/70533, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065, G03F 7/70658, G03F 7/70666, G03F 7/70675 and G03F 7/70683. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706839		Groups G03F 7/706839 and G03F 7/706841 are incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70491, G03F 7/705, G03F 7/70525, G03F 7/70533, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065, G03F 7/70658, G03F 7/70666, G03F 7/70675 and G03F 7/70683. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706843		Group G03F 7/706843 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/705, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065, G03F 7/70658, G03F 7/70675 and G03F 7/70683. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706845		Group G03F 7/706845 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70491, G03F 7/705, G03F 7/70508, G03F 7/70516,

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>Type*</u>	<u>Location</u>	<u>Old Warning</u>	<u>New/Modified Warning</u>
			G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065, G03F 7/70658, G03F 7/70675 and G03F 7/70683. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706847		Group G03F 7/706847 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065 and G03F 7/70675. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706849		Group G03F 7/706849 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065 and G03F 7/70675. All groups listed in this Warning should be considered in order to perform a complete search.
N	G03F 7/706851		Group G03F 7/706851 is incomplete pending reclassification of documents from groups G03F 7/70483, G03F 7/70608, G03F 7/70616, G03F 7/70625, G03F 7/70633, G03F 7/70641, G03F 7/7065 and G03F 7/70675. All groups listed in this Warning should be considered in order to perform a complete search.

*N = new warning, M = modified warning, D = deleted warning

NOTE: The "Location" column only requires the symbol PRIOR to the location of the warning. No further directions such as "before" or "after" are required.

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

C. New, Modified or Deleted Note(s)

SUBCLASS G03F - PHOTOMECHANICAL PRODUCTION OF TEXTURED OR PATTERNED SURFACES, e.g. FOR PRINTING, FOR PROCESSING OF SEMICONDUCTOR DEVICES; MATERIALS THEREFOR; ORIGINALS THEREFOR; APPARATUS SPECIALLY ADAPTED THEREFOR

<u>Type*</u>	<u>Location</u>	<u>Old Note</u>	<u>New/Modified Note</u>
M	G03F 7/70416	{Apparatus for photolithographical production of three dimensional images are further classified in group G03F 7/0037 and group B29C 64/00}	{Apparatus for photolithographical production of three-dimensional images are further classified in group G03F 7/0037}

*N = new note, M = modified note, D = deleted note

NOTE: The "Location" column only requires the symbol PRIOR to the location of the note. No further directions such as "before" or "after" are required.

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

2. B. DEFINITIONS QUICK FIX

Symbol	Location of change (e.g., section title)	Existing reference symbol or text	Action; New symbol; New text
G03F 2007/2067	Definition		<u>Delete</u> the entire Definition.

Notes:

Use this Definitions Quick Fix (DQF) table to:

- Delete an entire definition
- Delete an entire section
- Change a reference symbol
- Delete a reference symbol
- Delete text in a References section
- Correct one error in spelling, article use, or verb tense

Otherwise, use the standard template.

Reminder: Never delete F symbol definitions.

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

3. REVISION CONCORDANCE LIST (RCL)

<u>Type*</u>	<u>From CPC Symbol (existing)</u>	<u>To CPC Symbol(s)</u>
D	G03F2007/2067	<administrative transfer to G03F7/70>
C	G03F7/70375	G03F7/70375, G03F7/70
C	G03F7/70416	G03F7/70416, B29C64/00, B29C64/10, B29C64/106, B29C64/112, B29C64/118, B29C64/124, B29C64/129, B29C64/135, B29C64/141, B29C64/147, B29C64/153, B29C64/159, B29C64/165, B29C64/171, B29C64/176, B29C64/182, B29C64/188, B29C64/194, B29C64/20, B29C64/205, B29C64/209, B29C64/214, B29C64/218, B29C64/223, B29C64/227, B29C64/232, B29C64/236, B29C64/241, B29C64/245, B29C64/25, B29C64/255, B29C64/259, B29C64/264, B29C64/268, B29C64/273, B29C64/277, B29C64/282, B29C64/286, B29C64/291, B29C64/295, B29C64/30, B29C64/307, B29C64/314, B29C64/321, B29C64/329, B29C64/336, B29C64/343, B29C64/35, B29C64/357, B29C64/364, B29C64/371, B29C64/379, B29C64/386, B29C64/393, B29C64/40
C	G03F7/70483	G03F7/70483, G03F7/70605, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F7/70491	G03F7/70491, G03F7/70605, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706845
C	G03F7/705	G03F7/705, G03F7/70504, G03F7/70605, G03F7/70653, G03F7/70681, G03F7/70683, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845
C	G03F7/70508	G03F7/70508, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706845

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

Type*	From CPC Symbol (existing)	To CPC Symbol(s)
C	G03F7/70516	G03F7/70516, G03F7/70653, G03F7/70655, G03F7/706845
C	G03F7/70525	G03F7/70525, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841
C	G03F7/70533	G03F7/70533, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841
C	G03F7/70608	G03F7/70608, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F7/70616	G03F7/70616, G03F7/70653, G03F7/70655, G03F7/70666, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F7/70625	G03F7/70625, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F7/70633	G03F7/70633, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F7/70641	G03F7/70641, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

Type*	From CPC Symbol (existing)	To CPC Symbol(s)
C	G03F7/7065	G03F7/7065, G03F7/70653, G03F7/70655, G03F7/70681, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F7/70658	G03F7/70658, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845
C	G03F7/70666	G03F7/70666, G03F7/70681, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841
C	G03F7/70675	G03F7/70675, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845, G03F7/706847, G03F7/706849, G03F7/706851
C	G03F7/70683	G03F7/70683, G03F7/706831, G03F7/706833, G03F7/706835, G03F7/706837, G03F7/706839, G03F7/706841, G03F7/706843, G03F7/706845

* C = entries with modified file scope where reclassification of documents from the entries is involved; Q = new entries which are firstly populated with documents via administrative transfers from deleted (D) entries. Afterwards, the transferred documents into the Q entry will either stay or be moved to more appropriate entries, as determined by intellectual reclassification; D = deleted entries; F = frozen entries will be deleted once reclassification of documents from the entries is completed.

NOTES:

- Only C, D, F, and Q type entries are included in the table above.
- When multiple symbols are included in the “To” column, do not use ranges of symbols.
- For administrative transfer of documents, the following text should be used: “< administrative transfer to XX>”, “<administrative transfer to XX and YY simultaneously>”, or “<administrative transfer to XX, YY, ...and ZZ simultaneously>” when administrative transfer of the same documents is to more than one place.
- Administrative transfer to main trunk groups is assumed to be the source allocation type, unless otherwise indicated.
- Administrative transfer to 2000/Y series groups is assumed to be “additional information”.
- If needed, instructions for allocation type should be indicated within the angle brackets using the abbreviations “ADD” or “INV”: <administrative transfer to XX ADD>, <administrative transfer to XX INV>, or < administrative transfer to XX ADD, YY INV, ... and ZZ ADD simultaneously>.
- In certain situations, the “D” entries of 2000-series or Y-series groups may not require a destination (“To”) symbol, however it is required to specify “<no transfer>” in the “To” column for such cases.
- RCL is not needed for finalisation projects.

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

4. CHANGES TO THE CPC-TO-IPC CONCORDANCE LIST (CICL)

<u>CPC</u>	<u>IPC</u>	<u>Action*</u>
G03F 2007/2067		DELETE
G03F 7/70	G03F 7/00	UPDATED
G03F 7/70008	G03F 7/00	UPDATED
G03F 7/70016	G03F 7/00	UPDATED
G03F 7/70025	G03F 7/00	UPDATED
G03F 7/70033	G03F 7/00	UPDATED
G03F 7/70041	G03F 7/00	UPDATED
G03F 7/7005	G03F 7/00	UPDATED
G03F 7/70058	G03F 7/00	UPDATED
G03F 7/70066	G03F 7/00	UPDATED
G03F 7/70075	G03F 7/00	UPDATED
G03F 7/70083	G03F 7/00	UPDATED
G03F 7/70091	G03F 7/00	UPDATED
G03F 7/701	G03F 7/00	UPDATED
G03F 7/70108	G03F 7/00	UPDATED
G03F 7/70116	G03F 7/00	UPDATED
G03F 7/70125	G03F 7/00	UPDATED
G03F 7/70133	G03F 7/00	UPDATED
G03F 7/70141	G03F 7/00	UPDATED
G03F 7/7015	G03F 7/00	UPDATED
G03F 7/70158	G03F 7/00	UPDATED
G03F 7/70166	G03F 7/00	UPDATED
G03F 7/70175	G03F 7/00	UPDATED
G03F 7/70183	G03F 7/00	UPDATED
G03F 7/70191	G03F 7/00	UPDATED
G03F 7/702	G03F 7/00	UPDATED
G03F 7/70208	G03F 7/00	UPDATED
G03F 7/70216	G03F 7/00	UPDATED
G03F 7/70225	G03F 7/00	UPDATED
G03F 7/70233	G03F 7/00	UPDATED
G03F 7/70241	G03F 7/00	UPDATED
G03F 7/7025	G03F 7/00	UPDATED
G03F 7/70258	G03F 7/00	UPDATED
G03F 7/70266	G03F 7/00	UPDATED
G03F 7/70275	G03F 7/00	UPDATED
G03F 7/70283	G03F 7/00	UPDATED
G03F 7/70291	G03F 7/00	UPDATED
G03F 7/703	G03F 7/00	UPDATED
G03F 7/70308	G03F 7/00	UPDATED
G03F 7/70316	G03F 7/00	UPDATED
G03F 7/70325	G03F 7/00	UPDATED
G03F 7/70333	G03F 7/00	UPDATED

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>CPC</u>	<u>IPC</u>	<u>Action*</u>
G03F 7/70341	G03F 7/00	UPDATED
G03F 7/7035	G03F 7/00	UPDATED
G03F 7/70358	G03F 7/00	UPDATED
G03F 7/70366	G03F 7/00	UPDATED
G03F 7/70375	G03F 7/00	UPDATED
G03F 7/70383	G03F 7/00	UPDATED
G03F 7/70391	G03F 7/00	UPDATED
G03F 7/704	G03F 7/00	UPDATED
G03F 7/70408	G03F 7/00	UPDATED
G03F 7/70416	G03F 7/00	UPDATED
G03F 7/70425	G03F 7/00	UPDATED
G03F 7/70433	G03F 7/00	UPDATED
G03F 7/70441	G03F 7/00	UPDATED
G03F 7/7045	G03F 7/00	UPDATED
G03F 7/70458	G03F 7/00	UPDATED
G03F 7/70466	G03F 7/00	UPDATED
G03F 7/70475	G03F 7/00	UPDATED
G03F 7/70483	G03F 7/00	UPDATED
G03F 7/70491	G03F 7/00	UPDATED
G03F 7/705	G03F 7/00	UPDATED
G03F 7/70504	G03F 7/00	NEW
G03F 7/70508	G03F 7/00	UPDATED
G03F 7/70516	G03F 7/00	UPDATED
G03F 7/70525	G03F 7/00	UPDATED
G03F 7/70533	G03F 7/00	UPDATED
G03F 7/70541	G03F 7/00	UPDATED
G03F 7/7055	G03F 7/00	UPDATED
G03F 7/70558	G03F 7/00	UPDATED
G03F 7/70566	G03F 7/00	UPDATED
G03F 7/70575	G03F 7/00	UPDATED
G03F 7/70583	G03F 7/00	UPDATED
G03F 7/70591	G03F 7/00	UPDATED
G03F 7/706	G03F 7/00	UPDATED
G03F 7/70605	G03F 7/00	NEW
G03F 7/70608	G03F 7/00	UPDATED
G03F 7/70616	G03F 7/00	UPDATED
G03F 7/70625	G03F 7/00	UPDATED
G03F 7/70633	G03F 7/00	UPDATED
G03F 7/70641	G03F 7/00	UPDATED
G03F 7/7065	G03F 7/00	UPDATED
G03F 7/70653	G03F 7/00	NEW
G03F 7/70655	G03F 7/00	NEW
G03F 7/70658	G03F 7/00	UPDATED
G03F 7/70666	G03F 7/00	UPDATED

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>CPC</u>	<u>IPC</u>	<u>Action*</u>
G03F 7/70675	G03F 7/00	UPDATED
G03F 7/70681	G03F 7/00	NEW
G03F 7/70683	G03F 7/00	UPDATED
G03F 7/706831	G03F 7/00	NEW
G03F 7/706833	G03F 7/00	NEW
G03F 7/706835	G03F 7/00	NEW
G03F 7/706837	G03F 7/00	NEW
G03F 7/706839	G03F 7/00	NEW
G03F 7/706841	G03F 7/00	NEW
G03F 7/706843	G03F 7/00	NEW
G03F 7/706845	G03F 7/00	NEW
G03F 7/706847	G03F 7/00	NEW
G03F 7/706849	G03F 7/00	NEW
G03F 7/706851	G03F 7/00	NEW
G03F 7/70691	G03F 7/00	UPDATED
G03F 7/707	G03F 7/00	UPDATED
G03F 7/70708	G03F 7/00	UPDATED
G03F 7/70716	G03F 7/00	UPDATED
G03F 7/70725	G03F 7/00	UPDATED
G03F 7/70733	G03F 7/00	UPDATED
G03F 7/70741	G03F 7/00	UPDATED
G03F 7/7075	G03F 7/00	UPDATED
G03F 7/70758	G03F 7/00	UPDATED
G03F 7/70766	G03F 7/00	UPDATED
G03F 7/70775	G03F 7/00	UPDATED
G03F 7/70783	G03F 7/00	UPDATED
G03F 7/70791	G03F 7/00	UPDATED
G03F 7/708	G03F 7/00	UPDATED
G03F 7/70808	G03F 7/00	UPDATED
G03F 7/70816	G03F 7/00	UPDATED
G03F 7/70825	G03F 7/00	UPDATED
G03F 7/70833	G03F 7/00	UPDATED
G03F 7/70841	G03F 7/00	UPDATED
G03F 7/7085	G03F 7/00	UPDATED
G03F 7/70858	G03F 7/00	UPDATED
G03F 7/70866	G03F 7/00	UPDATED
G03F 7/70875	G03F 7/00	UPDATED
G03F 7/70883	G03F 7/00	UPDATED
G03F 7/70891	G03F 7/00	UPDATED
G03F 7/709	G03F 7/00	UPDATED
G03F 7/70908	G03F 7/00	UPDATED
G03F 7/70916	G03F 7/00	UPDATED
G03F 7/70925	G03F 7/00	UPDATED
G03F 7/70933	G03F 7/00	UPDATED

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

<u>CPC</u>	<u>IPC</u>	<u>Action*</u>
G03F 7/70941	G03F 7/00	UPDATED
G03F 7/7095	G03F 7/00	UPDATED
G03F 7/70958	G03F 7/00	UPDATED
G03F 7/70966	G03F 7/00	UPDATED
G03F 7/70975	G03F 7/00	UPDATED
G03F 7/70983	G03F 7/00	UPDATED
G03F 7/70991	G03F 7/00	UPDATED

*Action column:

- For an (N) or (Q) entry, provide an IPC symbol and complete the Action column with “NEW.”
- For an existing CPC main trunk entry or indexing entry where the existing IPC symbol needs to be changed, provide an updated IPC symbol and complete the Action column with “UPDATED.”
- For a (D) CPC entry or indexing entry complete the Action column with “DELETE.” IPC symbol does not need to be included in the IPC column.
- For an (N) 2000 series CPC entry which is positioned within the main trunk scheme (breakdown code) provide an IPC symbol and complete the action column with “NEW”.
- For an (N) 2000 series CPC entry positioned at the end of the CPC scheme (orthogonal code), with no IPC equivalent, complete the IPC column with “CPCONLY” and complete the action column with “NEW”.

NOTES:

- F symbols are not included in the CICL table above.
- T and M symbols are not included in the CICL table above unless a change to the existing IPC is desired.

CPC NOTICE OF CHANGES 1473

DATE: MAY 1, 2023

PROJECT RP10475

5. CROSS-REFERENCE LIST (CRL)

Definitions references impacted by this revision project

<u>Location of reference to be changed</u>	<u>Referenced subclass or group to be changed</u>	<u>Section of definition</u>	<u>Action; New reference symbol; New text</u>
B81C	G03F 2007/2067	Informative References	G03F 7/70
F16C 29/00	G03F 2007/2067	Application-oriented references	G03F 7/70
G03F 7/2051	G03F 2007/2067	Limiting references	G03F 7/70
G03F 7/213	G03F 2007/2067	Limiting references	G03F 7/70
G03F 7/22	G03F 2007/2067	Limiting references	G03F 7/70
G03F 7/24	G03F 2007/2067	Limiting references	G03F 7/70
G03F 9/70	G03F 2007/2067	Informative References	G03F 7/70
H01J 37/3174	G03F 2007/2067	Informative References	G03F 7/70
H01J 37/32	G03F 2007/2067	Informative References	G03F 7/70

NOTES:

- The CRL tables above are used for changes to locations **outside** of the project scope. Changes to references in scheme titles or definitions **inside** the project scope will be reflected in the “scheme change” template or one of the “definition” templates.
- In addition to other changes proposed in the tables above, in the column titled “Referenced subclass or group to be changed,” **referenced** D symbols should indicate an action of “delete” or should indicate a replacement symbol and **referenced** F symbols should indicate a replacement symbol.
- When a reference is deleted, text related to that reference will also be deleted unless other references or a range of references associated with the same text remain.